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10 Response
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U.S. GOVERNMENT 23001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Chandra V. Mouli

§ Group Art Unit: 2812 JU 23

Serial No.: 09/379,092

TECHNICAL SUPPORT CENTER 2000

Filed: August 23, 1999

§ Examiner: R. Pompey

For: FORMING SIDEWALL OXIDE
LAYERS FOR TRENCH
ISOLATION

§
§
§ Atty. Dkt. No.: MICT-0042-US

Box AF
Commissioner for Patents
Washington DC 20231

REPLY TO FINAL REJECTION

Siri

In response to the office action mailed June 28, 2001,
please consider the following remarks.

Remarks

Claims 1 and 33 stand rejected under §102 based on the reference to Hong. (The taking of official notice was only with respect to the §103 rejection of the dependent claims.)

Reconsideration of the §102 rejection of claims 1 and 33 is requested. Claim 1 calls for implanting impurities which enhance the oxidation of said structure beyond that which would be expected from crystallographic damage effects. The final rejection states that "Hong is silent on what produces the oxidation enhancement by implanting dopant species into the substrate. Therefore, it is not disclosed whether it is crystallographic damage . . ." In view of this statement, it is clear that the §102 rejection of claim 1 is not appropriate.

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Lisa O'Sullivan
Lisa O'Sullivan